Plasma-enhanced Atomic Layer Deposition of Molybdenum Compounds Thin Films Using $Mo(CO)_6$ with Various Plasma Gases

Jeong-Hun Choi, Seung-Won Lee, Cheol-Min Hyun and Ji-Hoon Ahn
Department of Electronic Material Engineering, Korea Maritime and Ocean University,
E-mail : ajh1820@kmou.ac.kr

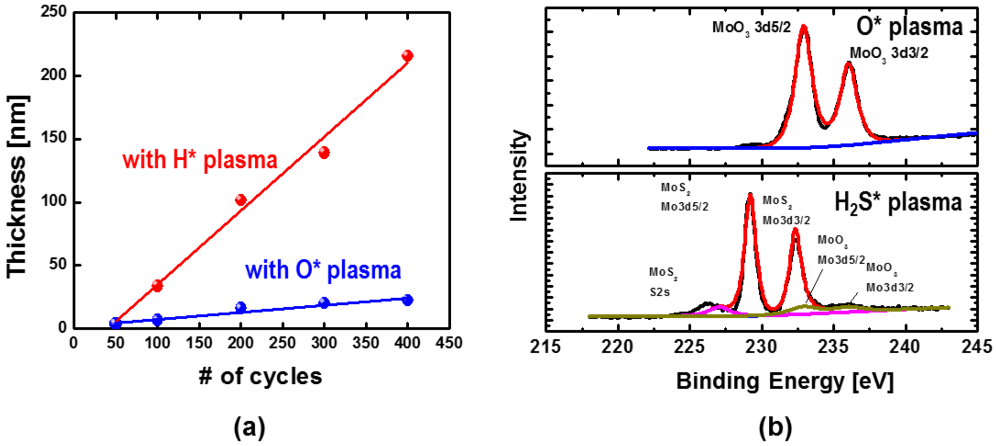

Fig1. (a) Deposition rate of metallic Mo and MoO_3 thin films, (b) XPS spectra of MoO_3, MoS_2 deposited by PEALD.